

Title (en)  
LITHOGRAPHY SYSTEM AND PROJECTION METHOD

Title (de)  
LITHOGRAPHIESYSTEM UND PROJEKTIONSVERFAHREN

Title (fr)  
SYSTEME DE LITHOGRAPHIE ET PROCEDE DE PROJECTION

Publication  
**EP 1943561 A1 20080716 (EN)**

Application  
**EP 06783923 A 20060914**

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Abstract (en)  
[origin: WO2007032671A1] The invention relates to a lithography system in which an electronic image pattern is delivered to an exposure tool for projecting an image on a target surface, said exposure tool comprising a control unit for controlling exposure projections, said control unit at least partly being included in the projection space of the said exposure tool, and being provided with control data by means of light signals, said light signals being coupled in to said control unit by using a free space optical interconnect comprising modulated light beams that are emitted to a light sensitive part of said control unit, wherein the modulated light beams are coupled in to said light sensitive part using a holed mirror for on axis incidence of said light beams on said light sensitive part, the hole or, alternatively, holes of said mirror being provided for passage of said exposure projections.

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